L Number	Hits	Search Text	DB	Time stamp
1	14	(((optical with (process or proximity) with correction) and (proximity with effect with correction)) and ((node or locus or vertex or verticies or intersection) same (detect$5 or find$3 or locate$4)) and ((node or locus or vertex or verticies or intersection) same (delet$5 or eras$3 or remov$4))) and (line or segment)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/11/01 11:38
2	15	(716/21.ccls. and ((offset or shift or move or shrink) same (line or segment))) and ((delet$4 or remov$4 or eliminat$4) with (vertex orverticies or interconnect$5 or locus or cluster or point))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/11/01 11:38
-	24	yoshizawa-keiji.in.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/10/31 18:08
-	8452	opc or (optical with (process or proximity) with correction)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/10/29 21:15
-	126	(opc or (optical with (process or proximity) with correction)) and ((node or locus or vertex or verticies or intersection) same (detect$5 or find$3 or locate$4)) and ((node or locus or vertex or verticies or intersection) same (delet$5 or eras$3 or remov$4))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/10/29 21:27
-	1	((opc or (optical with (process or proximity) with correction)) and ((node or locus or vertex or verticies or intersection) same (detect$5 or find$3 or locate$4)) and ((node or locus or vertex or verticies or intersection) same (delet$5 or eras$3 or remov$4))) and 6687885.pn.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/10/29 19:37
-	1	((opc or (optical with (process or proximity) with correction)) and ((node or locus or vertex or verticies or intersection) same (detect$5 or find$3 or locate$4)) and ((node or locus or vertex or verticies or intersection) same (delet$5 or eras$3 or remov$4))) and (((ocr or (optical with (process or proximity) with recognition)) and ((node or locus or vertex or verticies or intersection) same (detect$5 or find$3 or locate$4)) and ((node or locus or vertex or verticies or intersection) same (delet$5 or eras$3 or remov$4))) and (line or segment))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/10/29 19:38
-	116	((opc or (optical with (process or proximity) with correction)) and ((node or locus or vertex or verticies or intersection) same (detect$5 or find$3 or locate$4)) and ((node or locus or vertex or verticies or intersection) same (delet$5 or eras$3 or remov$4))) and (line or segment)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/10/29 19:40
-	2360	(optical with (process or proximity) with correction)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/10/29 19:39
-	45	((optical with (process or proximity) with correction)) and ((node or locus or vertex or verticies or intersection) same (detect$5 or find$3 or locate$4)) and ((node or locus or vertex or verticies or intersection) same (delet$5 or eras$3 or remov$4))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/10/29 20:40

-	44	(((optical with (process or proximity) with correction)) and ((node or locus or vertex or verticies or intersection) same (detect$5 or find$3 or locate$4)) and ((node or locus or vertex or verticies or intersection) same (delet$5 or eras$3 or remov$4))) and (line or segment)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/10/29 19:59
-	565	716/21.ccls.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/10/29 20:40
-	162	716/21.ccls. and ((offset or shift or move or shrink) same (line or segment))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/10/29 21:26
-	54	(716/21.ccls. and ((offset or shift or move or shrink) same (line or segment))) and ((delet$4 or remov$4 or eliminat$4) same (vertex orverticies or interconnect$5 or locus or cluster or point))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/10/29 20:43
-	15	(716/21.ccls. and ((offset or shift or move or shrink) same (line or segment))) and ((delet$4 or remov$4 or eliminat$4) with (vertex orverticies or interconnect$5 or locus or cluster or point))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/11/01 11:37
-	0	ichiro-hagino.in. and satoru-akutagawa.in.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/10/29 21:01
-	511	(optical with (process or proximity) with correction) and (proximity with effect with correction)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/10/29 21:26
-	14	((optical with (process or proximity) with correction) and (proximity with effect with correction)) and ((node or locus or vertex or verticies or intersection) same (detect$5 or find$3 or locate$4)) and ((node or locus or vertex or verticies or intersection) same (delet$5 or eras$3 or remov$4))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/10/29 21:17
-	14	(((optical with (process or proximity) with correction) and (proximity with effect with correction)) and ((node or locus or vertex or verticies or intersection) same (detect$5 or find$3 or locate$4)) and ((node or locus or vertex or verticies or intersection) same (delet$5 or eras$3 or remov$4))) and (line or segment)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/11/01 11:37
-	320	(optical with (process or proximity) with correction) and (resiz$5 or shrink$5)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/10/29 21:26
-	152	((optical with (process or proximity) with correction) and (resiz$5 or shrink$5)) and ((offset or shift or move or shrink) same (line or segment))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/10/29 21:26
-	7	((optical with (process or proximity) with correction) and (resiz$5 or shrink$5)) and ((node or locus or vertex or verticies or intersection) same (detect$5 or find$3 or locate$4)) and ((node or locus or vertex or verticies or intersection) same (delet$5 or eras$3 or remov$4))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/10/29 21:27
-	41	broda-$.xa. and optical	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/10/31 18:08

-	30	((optical with (process or proximity) with recognition)) and ((node or locus or vertex or verticies or intersection) same (detect$5 or find$3 or locate$4)) and ((node or locus or vertex or verticies or intersection) same (delet$5 or eras$3 or remov$4))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/11/01 10:32

Results of Search "L2"

	Document ID	Issue Date	Title	Current OR	Current XRef
1	US 20040209176 A1	20041021	Model-based data conversion	430/5	430/322; 716/19; 716/21
2	US 20040161679 A1	20040819	Full sized scattering bar alt-PSM technique for IC manufacturing in sub-resolution era	430/5	716/19; 716/21
3	US 20020160278 A1	20021031	Method for designing photolithographic reticle layout, reticle, and photolithographic process	430/5	430/322; 716/19; 716/21
4	US 20020132174 A1	20020919	Self-aligned fabrication technique for tri-tone attenuated phase-shifting masks	430/5	430/311; 430/312; 430/313; 430/394; 716/21
5	US 20020015899 A1	20020207	Hybrid phase-shift mask	430/5	430/322; 716/19; 716/21
6	US 6792590 B1	20040914	Dissection of edges with projection points in a fabrication layout for correcting proximity effects	716/19	430/5; 716/21
7	US 6785879 B2	20040831	Model-based data conversion	716/21	430/5; 716/19; 716/7; 716/8
8	US 6711732 B1	20040323	Full sized scattering bar alt-PSM technique for IC manufacturing in sub-resolution era	716/19	716/21

	Document ID	Issue Date	Title	Current OR	Current XRef
9	US 6625801 B1	20030923	Dissection of printed edges from a fabrication layout for correcting proximity effects	716/19	716/21
10	US 6546543 B1	20030408	Method of displaying, inspecting and modifying pattern for exposure	716/21	
11	US 6543045 B2	20030401	Method for detecting and automatically eliminating phase conflicts on alternating phase masks	716/21	716/19; 716/20
12	US 6539521 B1	20030325	Dissection of corners in a fabrication layout for correcting proximity effects	716/4	716/19; 716/21
13	US 6493866 B1	20021210	Phase-shift lithography mapping and apparatus	716/21	430/396; 430/5; 716/19; 716/4
14	US 5124927 A	19920623	Latent-image control of lithography tools	700/121	250/491.1; 356/394; 356/401; 702/94; 716/21
15	US 4559603 A	19851217	Apparatus for inspecting a circuit pattern drawn on a photomask used in manufacturing large scale integrated circuits	716/5	250/491.1; 250/492.2; 257/E21.211; 356/237.5; 356/394; 716/21

Results of Search "L1"

	Document ID	Issue Date	Title	Current OR	Current XRef
1	US 20040191650 A1	20040930	Phase shift masking for complex patterns with proximity adjustments	430/5	716/19
2	US 20030126582 A1	20030703	Pattern correction method and manufacturing method of semiconductor device	716/21	700/121; 716/19
3	US 20030023939 A1	20030130	METHOD AND APPARATUS FOR ANALYZING A LAYOUT USING AN INSTANCE-BASED REPRESENTATION	716/3	716/19; 716/4; 716/5; 716/8
4	US 20020127479 A1	20020912	Phase shift masking for complex patterns with proximity adjustments	430/5	
5	US 20020026624 A1	20020228	Correction of layout pattern data during semiconductor patterning process	716/11	716/10; 716/4
6	US 6792590 B1	20040914	Dissection of edges with projection points in a fabrication layout for correcting proximity effects	716/19	430/5; 716/21
7	US 6777138 B2	20040817	Mask product made by selection of evaluation point locations based on proximity effects model amplitudes for correcting proximity effects in a fabricat layout	430/5	

	Document ID	Issue Date	Title	Current OR	Current XRef
8	US 6733929 B2	20040511	Phase shift masking for complex patterns with proximity adjustments	430/5	430/30; 716/19
9	US 6687885 B2	20040203	Correction of layout pattern data during semiconductor patterning process	716/5	716/11; 716/19
10	US 6625801 B1	20030923	Dissection of printed edges from a fabrication layout for correcting proximity effects	716/19	716/21
11	US 6560766 B2	20030506	Method and apparatus for analyzing a layout using an instance-based representation	716/19	716/11; 716/17; 716/21; 716/4; 716/5; 716/8
12	US 6539521 B1	20030325	Dissection of corners in a fabrication layout for correcting proximity effects	716/4	716/19; 716/21
13	US 6453457 B1	20020917	Selection of evaluation point locations based on proximity effects model amplitudes for correcting proximity effects in a fabrication layout	716/19	430/5; 716/20
14	US 5923566 A	19990713	Phase shifted design verification routine	716/21	430/311; 430/322; 430/5

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lsi <and> mask <and> pattern Search

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JNL = Journal or Magazine **CNF** = Conference **STD** = Standard

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1 **An automated system for LSI fine pattern inspection based on comparison of SEM images and CAD data**
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Robotics and Automation, 1995. Proceedings., 1995 IEEE International Confer on , Volume: 1 , 21-27 May 1995
Pages:544 - 549 vol.1

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2 **HARP: FORTRAN to silicon [compilation system]**
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5 **New approach to resolution limit and advanced image formation techniques in optical lithography**
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8 **Subhalf-micron gate GaAs MESFET process using phase-shifting-ma technology**
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12 **Inspection of critical dimension- and transmission uniformity of co patterns by DUV imaging and regression algorithm**
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13 **EYESEE: A machine vision system for inspection of integrated circu chips**
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optical <and> proximity <and> correction Search

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Results Key:
JNL = Journal or Magazine **CNF** = Conference **STD** = Standard

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1 **High accurate optical proximity correction under the influences of le aberration in 0.15 µm logic process**
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9 **Identify Optical Proximity Correction (OPC) issue in 0.13 /spl mu/m technology development**
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15 **Layout design methodologies for sub-wavelength manufacturing**
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16 **A statistical gate CD control including OPC**
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